

ENEL5808
Signal Processing Electronics
Mid-Term Examination

Student Name _____

Student Number _____

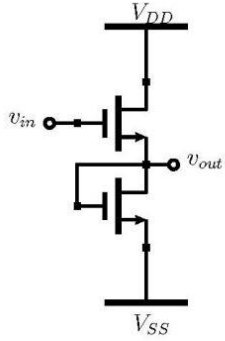
Oct. 26,2010 5:30PM - 7:00PM

R. Mason

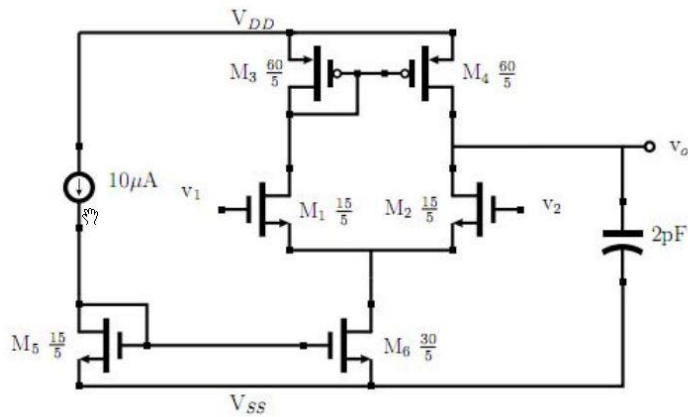
answer all questions on sheet provided, one 8.5 x 11 crib sheet allowed

1. (5 points) Multiple Choice, Circle BEST answer
- (a) We can add impurities to the silicon substrate using:
- (i) oxidation
 - (ii) photomasking
 - (iii) ion implantation
 - (iv) sputtering
- (b) Compared to a standard current mirror, a cascode current mirror generally has:
- (i) smaller output swing
 - (ii) smaller output impedance
 - (iii) fewer transistors
 - (iv) smaller current
- (c) An advantage of thin film resistors compared to an implanted resistors is:
- (i) higher yield
 - (ii) higher TEMPCOs
 - (iii) lower cost
 - (iv) wider range of values
- (d) The body effect is accounted for by what component in the small signal model:
- (i) g_{sb}
 - (ii) $g_m V_{gs}$
 - (iii) g_{ds}
 - (iv) $g_s V_s$
- (e) A CMOS transistor is formed by the overlap of which two masks:
- (i) polysilicon and contact
 - (ii) polysilicon and active
 - (iii) nplus and active
 - (iv) metal and polysilicon
2. (10 points) Short Answer
- (a) Draw the cross section of a CMOS inverter in an N-well process and show how a substrate PNP transistor could be formed.

3. (5 points) For the following circuit assuming all transistors are in saturation and have $W/L = 100\mu\text{m}/1.5\mu\text{m}$, $u_n C_{ox} = 80 \mu\text{A}/\text{V}^2$, $u_p C_{ox} = 40\mu\text{A}/\text{V}^2$, $I_D = 100\mu\text{A}$, $r_{ds-n} (\text{ohms}) = r_{ds-p} (\text{ohms}) = 6,000L (\mu\text{m})/I_d (\text{mA})$, Ignoring the body effect, what is the gain of this stage?

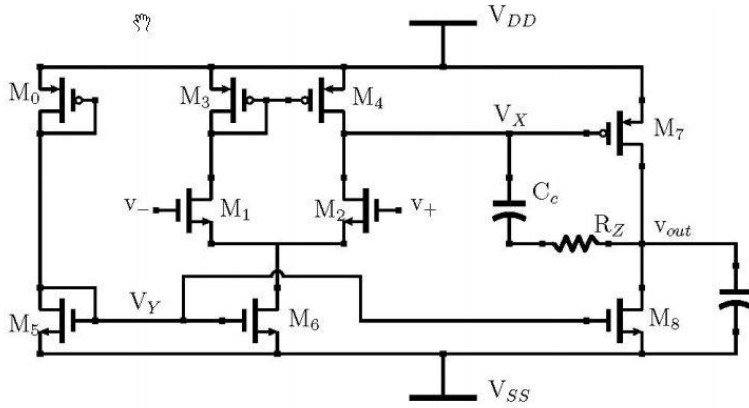


4. (4 points) What is this circuit? Draw the DC transfer curve of v_o vs. $(v_1 - v_2)$.



5. (6 points) What are the following circuits? Explain the purpose of each transistor in the circuits.

(a)



(b)

